

# Fully Optical in Operando Investigation of Ambient Condition Electrical Switching in MoS<sub>2</sub> Nanodevices

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MoS<sub>2</sub> nanoswitches have shown superb ultralow switching energies without excessive leakage currents. However, the debate about the origin and volatility of electrical switching is unresolved due to the lack of adequate nanoimaging of devices in operando. Here, three optical techniques are combined to perform the first noninvasive in situ characterization of nanosized MoS<sub>2</sub> devices. This study reveals volatile threshold resistive switching due to the intercalation of metallic atoms from electrodes directly between Mo and S atoms, without the assistance of sulfur vacancies. A “semi-memristive” effect driven by an organic adlayer adjacent to MoS<sub>2</sub> is observed, which suggests that nonvolatility can be achieved by careful interface engineering. These findings provide a crucial understanding of nanoprocess in vertically biased MoS<sub>2</sub> nanosheets, which opens new routes to conscious engineering and optimization of 2D electronics.

## 1. Introduction

Electrical switches based on MoS<sub>2</sub> nanosheets have attracted a lot of attention<sup>[1–20]</sup> due to their ultralow switching energies<sup>[14,20]</sup> without excessive leakage currents for few-nanometers thick devices.<sup>[13,16]</sup> Moreover, some of them exhibit nonvolatile (memristive) switching<sup>[12,14,17]</sup> which facilitates neuromorphic computing capable of reducing energy consumption in IT by up to 80%.<sup>[21,22]</sup> Nevertheless, most groups observe only a volatile effect<sup>[23–26]</sup> and nonvolatility is achieved by oxidation<sup>[6,12]</sup> and sulfurization of MoS<sub>2</sub> bulk<sup>[5]</sup> or by stacking MoS<sub>2</sub> monolayers.<sup>[17]</sup>

To achieve commercial importance, vertical nanoscale devices (with areas < 10<sup>4</sup> nm<sup>2</sup>) are desirable, as they provide the lowest switching voltages and highest integration densities.<sup>[27]</sup> On the contrary, most of the switching behaviors are studied in microsized devices<sup>[1–17]</sup> although stochastic switching

processes are different for microscale and nanoscale electrodes.<sup>[27]</sup> To our knowledge, only two works investigate MoS<sub>2</sub> biased vertically with nanosized electrodes.<sup>[18,20]</sup> Both report volatile conductive filaments formed by metallic atoms diffusing from electrodes into sulfur vacancies (V<sub>S</sub>).<sup>[18,20]</sup> However, those measurements are performed in vacuum conditions, again leading to different switching dynamics and device performances of the ones observed in the air.<sup>[13,18,20,27]</sup> Therefore, due to the lack of adequate imaging technologies capable of peering into commercially relevant devices, i.e., at the nanoscale and in ambient conditions, the origin and the volatility of electrical switching in MoS<sub>2</sub>

remains unclear.<sup>[16,27]</sup>

We have recently developed the first non-invasive technique able to track material's morphology in situ, at the nanoscale, and in ambient conditions, via plasmon-enhanced dark field (DF) nanospectroscopy.<sup>[28–30]</sup> Here, we expand it with additional capabilities offered by nano-Raman and nano-photoluminescence to study the switching mechanism in MoS<sub>2</sub>. The method's principle is presented in **Figure 1a**. An 80 nm gold nanoparticle (AuNP) placed in the vicinity of a gold substrate is illuminated with white light ( $\lambda \approx 400\text{--}900$  nm) to produce plasmonic resonances within the AuNP (single mode) and in a spacer between AuNP and the substrate (gap mode).<sup>[31,32]</sup> The resonances are detected using DF scattering microscope configuration and the gap mode's wavelength and intensity depend on the spacer's refractive index, thickness, and geometry.<sup>[31,32]</sup> Using a AuNP as a nanosized ( $\approx 700$  nm<sup>2</sup>) top contact of an electrical switch<sup>[29,33]</sup> results in a strong field enhancement localized within the nanoscale switching channel. This greatly enhances both Raman and photoluminescence (PL) signals,<sup>[34]</sup> conveniently highlighting the otherwise undetectable nanoscale switching dynamics.

Many switching mechanisms are proposed in the literature for MoS<sub>2</sub>, as summarized in **Table 1**. Among these are migrations of sulfur vacancies (V<sub>S</sub>),<sup>[3,9,10]</sup> movements of oxygen in oxidized MoS<sub>2</sub>,<sup>[6,12]</sup> charge trapping and detrapping,<sup>[2]</sup> phase change from semiconducting (2H) to metallic (1T'),<sup>[4,7]</sup> and metal ions intercalating from electrodes.<sup>[5,13,17,18,20]</sup> We note that all the above mechanisms would trigger changes in optical signals (Raman, PL) which are detectable with our experimental capabilities. In particular, the density of V<sub>S</sub>, which are observed in all MoS<sub>2</sub> nanosheets studied by transmission electron microscopy (TEM),<sup>[36–38]</sup> is correlated to the PL peak at  $\approx 750$  nm,<sup>[39,40]</sup> the intensity ratio of MoS<sub>2</sub>'s A/B excitons<sup>[39,41]</sup>

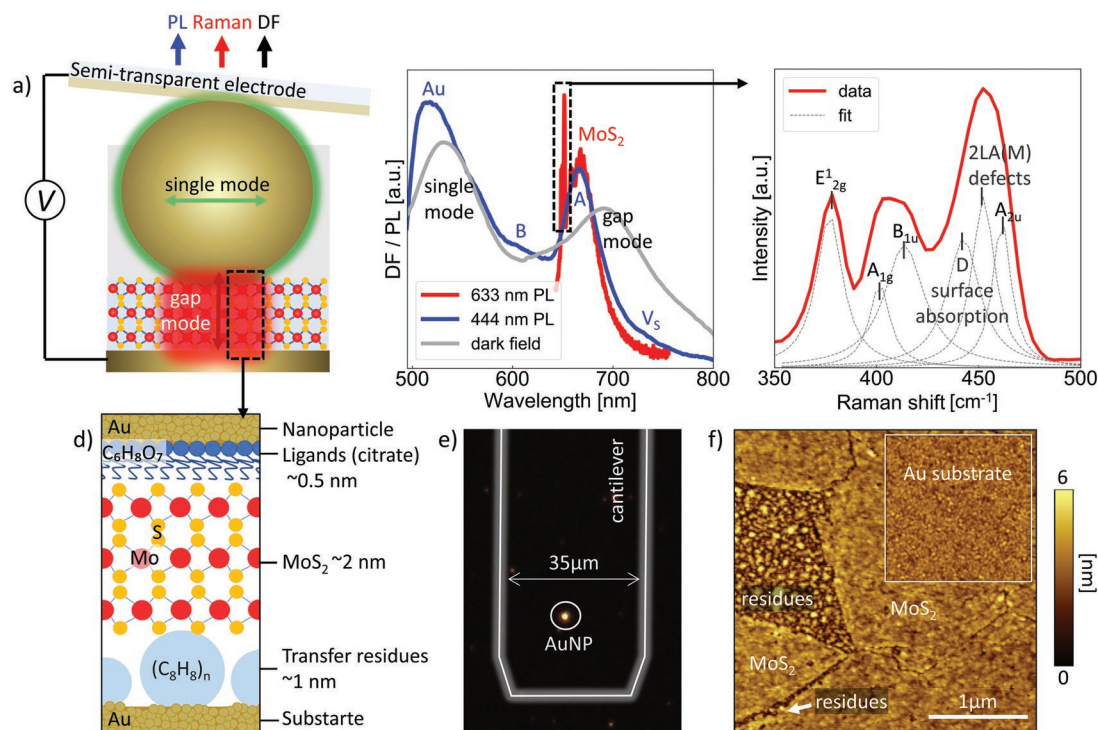
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**Figure 1.** a) Device layout. b) Optical characterization of MoS<sub>2</sub> switch by white light (DF), 633 nm laser (PL, Raman – marked by a dashed rectangle) and 444 nm laser (PL) illumination. The plasmonic gap mode enhances MoS<sub>2</sub>'s PL, while the single mode boosts Au luminescence. c) Zoom on the resonant Raman part of the 633 nm excitation.<sup>[35]</sup> d) Scheme of a switching channel: MoS<sub>2</sub> is sandwiched between transfer residues and ligands. e) Dark field microscopy picture of the device contacted by a cantilever. f) AFM map of MoS<sub>2</sub> before the deposition of nanoparticle top electrodes. Rough surface under MoS<sub>2</sub> suggests polymer residues and not substrate damage, as verified by examining Au substrate in the area without MoS<sub>2</sub> (insert).

and the separation between A<sub>1g</sub> and E<sub>2g</sub><sup>1</sup> Raman modes.<sup>[39,42]</sup> V<sub>S</sub> and V<sub>o</sub> p-dope MoS<sub>2</sub> quenching PL<sup>[40,43]</sup> and hence switching processes associated with n-doping (charge trapping<sup>[2,6,11]</sup> and V<sub>o</sub> migration<sup>[6,12]</sup>) would mitigate the drop in PL.<sup>[40,43,44]</sup>

Moreover, n-doping modifies A<sub>1g</sub> Raman mode.<sup>[45]</sup> Electrical switching triggered by phase transitions or adsorption of water/air<sup>[6]</sup> would result in new Raman peaks.<sup>[4,7,35,46]</sup> Lastly, intercalation of Au into MoS<sub>2</sub> would quench optical signals.<sup>[20,47]</sup>

**Table 1.** Review of mechanisms explaining resistivity changes in MoS<sub>2</sub> nanoswitches, with expected changes in Raman and PL spectra of MoS<sub>2</sub>.

Proposed mechanism	Diagram	Expected changes in Raman	Expected changes in PL
Metal intercalation into V <sub>S</sub> . <sup>[5,13,17,18,20]</sup>		Signal quenched by contact with Au. <sup>[48]</sup> Modification of A <sub>1g</sub> and 2LA(M) modes associated with V <sub>S</sub> . <sup>[42,49,50]</sup>	Signal quenched by contact with Au. <sup>[20,47]</sup> Modification of V <sub>S</sub> peak at ≈750 nm. <sup>[39,40]</sup>
V <sub>S</sub> migration near grain boundaries. <sup>[3,9,10]</sup>		Surge in V <sub>S</sub> increases separation between A <sub>1g</sub> and E <sub>2g</sub> <sup>1</sup> modes. <sup>[42]</sup>	Risen V <sub>S</sub> gives new peak at ≈750 nm, <sup>[39,40]</sup> quenches PL, <sup>[39]</sup> reduces A/B exciton ratio. <sup>[39,41]</sup>
Phase change from 2H to 1T'. <sup>[4,7]</sup>		Raman modes for 1T': 200, 225, 355 cm <sup>-1</sup> ; modes for 2H: 384, 408cm <sup>-1</sup> . <sup>[4,46]</sup>	1T' metallic phase shows PL. <sup>[46]</sup>
Migration of oxygen defects in oxidized MoS <sub>2</sub> . <sup>[6,12,51]</sup>		Absorption of O <sub>2</sub> produces mode at ≈440cm <sup>-1</sup> <sup>[35]</sup> and blue-shifts A <sub>1g</sub> mode. <sup>[43]</sup>	Absorption of O <sub>2</sub> boosts PL's intensity. <sup>[43,44]</sup>
Charge trapping and detrapping. <sup>[2,6,11]</sup>		n-doping softens and broadens A <sub>1g</sub> mode. <sup>[42]</sup>	n-doping enhances PL because MoS <sub>2</sub> is naturally p-doped by V <sub>S</sub> . <sup>[40,52]</sup>

Our aim is to investigate morphological changes occurring in electrically biased MoS<sub>2</sub> nanosheets by spectroscopical observation of defects dynamics. Here, for the first time, we not only access both PL and Raman in operando, but we additionally support those optical signatures with DF spectroscopy for a true real time investigation of MoS<sub>2</sub> switching mechanisms.

## 2. Results

### 2.1. Material Characterization

We fabricate cells by transferring MoS<sub>2</sub> onto Au substrate and drop-casting AuNP as a top electrode (see Figure 1a). The AuNP is electrically biased via a conductive but optically semi-transparent cantilever, as presented in Figure 1e. A scheme of electrical contacting setup is shown in Figure S1 in the Supporting Information.

Optical characterization of the MoS<sub>2</sub> switch (Figure 1b) is obtained both by broad incoherent white light illumination (400–900 nm) to investigate plasmonic resonances (DF), and laser irradiation to enable PL with two different excitation wavelengths (444 and 633 nm) and Raman with 633 nm excitation. DF scattering shows a gap mode at ≈700 nm and a single mode at ≈550 nm, enhancing PL emissions from MoS<sub>2</sub> (668, 615 nm<sup>[39,53]</sup>) and Au (525, 557 nm<sup>[54,55]</sup>), respectively. With 444 nm excitation laser, we observe a small peak at ≈740 nm in the PL signal which we attribute to V<sub>S</sub>.<sup>[40]</sup>

MoS<sub>2</sub> excitons A and B (668 and 615 nm, respectively) are in resonance with the 633 nm laser wavelength which we use for our Raman characterization. As a result, we observe resonant Raman,<sup>[35]</sup> marked by a dashed rectangle in Figure 1b. It enhances the otherwise too dim Raman signal coming from just few layers of MoS<sub>2</sub> and enables observation of modes dynamics otherwise too weak to be tracked.<sup>[56]</sup> The collected resonant Raman is magnified in Figure 1c. It suggests the presence of V<sub>S</sub> (mode 2LA(M) at 452 cm<sup>-1</sup> activated by defects<sup>[49]</sup>) and residues bonded to MoS<sub>2</sub>'s surface (mode D at 440 cm<sup>-1</sup>).<sup>[35]</sup> It can be further used to estimate MoS<sub>2</sub> thickness, as spacing between E<sub>1g</sub> and A<sub>1g</sub> modes is thickness dependent.<sup>[35]</sup> In the device presented in this work we find a spacing of 24 cm<sup>-1</sup>, corresponding to three layers MoS<sub>2</sub>, i.e., thickness of about 2 nm.<sup>[35,57]</sup> In total, we tested ≈40 cells with 1–3 layers of MoS<sub>2</sub> (verified by PL and Raman) and the change in optical signals with switching was analogous for all thicknesses.

Since moisture and fabrication residues influence electrical switches,<sup>[18,58]</sup> we make sure to consider all possible species present in our cell, as presented in Figure 1d. The residues are hardly ever mentioned in literature related to 2D materials because standard imaging techniques are either destructive to nanosized organics (electron microscopies) or residues signal is overshadowed by atmospheric contaminants (X-ray photoelectron and energy dispersive spectroscopies). Consequently, we use our novel optical technique, highlighting its clear advantage in transfer residues detection. It combines four independent methods, such as Raman, PL, DF, and atomic force microscopy (AFM). First, we consider residues associated with AuNP drop-casting. AuNPs are stabilized by citrate ligands (C<sub>6</sub>H<sub>8</sub>O<sub>7</sub>)<sup>[59]</sup> and we confirm their presence by Raman and DF

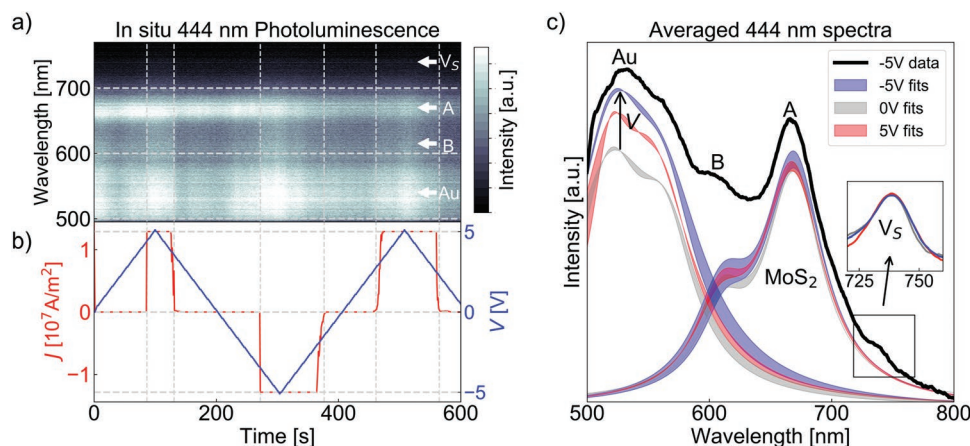
measurements on a control sample consisting of AuNP drop casted directly on Au substrate (Figure S2, Supporting Information). The resulting DF mode's wavelength implies a gap of ≈0.5 nm, which matches literature values.<sup>[60]</sup> Second, we investigate possible organic transfer residues (polystyrene – (C<sub>8</sub>H<sub>8</sub>)<sub>n</sub>) surrounding MoS<sub>2</sub>.<sup>[61]</sup> We expect an adlayer between MoS<sub>2</sub> and Au because MoS<sub>2</sub>'s PL signal would be otherwise quenched by a direct contact with Au.<sup>[47]</sup> Indeed, AFM scans (Figure 1f; Figure S3, Supporting Information) reveal different surface roughness for MoS<sub>2</sub> (≈0.4 nm), Au substrate beneath MoS<sub>2</sub> (≈1.2 nm), and Au in region without MoS<sub>2</sub> (≈0.6 nm). Since the “bumps” on Au occur only in vicinity of MoS<sub>2</sub>, we conclude that they are not due to damaged Au substrate but are polymer residues.<sup>[62]</sup> Smooth surface of MoS<sub>2</sub> indicates that polystyrene is surprisingly only under MoS<sub>2</sub> and not on top of it (see arrow in Figure 1f). Moreover, the AFM step of 2 nm (Figure S3a, Supporting Information) corresponds to three layers of MoS<sub>2</sub> (previously verified by Raman) which implies that no additional layer is present on top of MoS<sub>2</sub>. Knowing that the combined thickness of MoS<sub>2</sub> + ligands is ≈2.5 nm (verified by Raman, DF, and AFM, see Figure 1c and Section SB in the Supporting Information), with FDTD framework we calculate that the observed resonance at ≈700 nm (Figure 1b) would require additional polymer thickness of ≈1 nm, which corresponds to the observed surface roughness (≈1.2 nm).

### 2.2. In Situ 444 nm Photoluminescence

We track the evolution of the PL signal (Figure 2a) while the device is biased with triangular field profiles between +/–5 V (Figure 2b). A link between PL intensity and applied voltage is present and further highlighted by averaging over many switching cycles (Figure 2c). The individual optical responses of Au, MoS<sub>2</sub> and V<sub>S</sub> are extracted by Lorentzian fits (Figure 2c: blue, red, and grey for –5, 5, and 0 V, respectively). The most prominent change triggered by both positive and negative voltage is the rise in Au luminescence (≈540 nm), suggesting more Au atoms present in the gap between electrodes, i.e., Au intercalation into MoS<sub>2</sub>. The 540 nm luminescence increase is greater for V < 0 when Au is pulled from a substrate rather than from AuNP, due to ligands surrounding the top AuNP limiting Au atoms drift. The PL peak at 740 nm, linked to V<sub>S</sub> content,<sup>[39,40]</sup> is unaffected by voltage (insert in Figure 2c). Therefore, contrary to previous suggestions (Table 1),<sup>[13,18,20]</sup> V<sub>S</sub> seem not to take part in the switching process. Although MoS<sub>2</sub>'s A and B excitons are visible in the collected data, they overlap with a strong Au luminescence background, which results in a Laurentian fitting characterized by statistical errors large enough to prevent making any conclusion on the MoS<sub>2</sub> PL behavior with voltage.

### 2.3. In Situ 633 nm Laser Excitations

To eliminate the effect of Au background, we additionally collect PL using a 633 nm excitation laser (Figure 3). The gain in using a 633 nm excitation laser is twofold as, on top of enabling in operando resonant Raman, it also allows focusing on the MoS<sub>2</sub>



**Figure 2.** In situ PL characterization (444 nm excitation laser) of a vertically biased MoS<sub>2</sub> nanosheet: a) PL signal evolution in time, b) applied voltages with measured current densities ( $J$ ), and c) PL spectra at 5, 0, and  $-5$  V averaged over many switching cycles, with shadows indicating statistical errors in the fitting process.

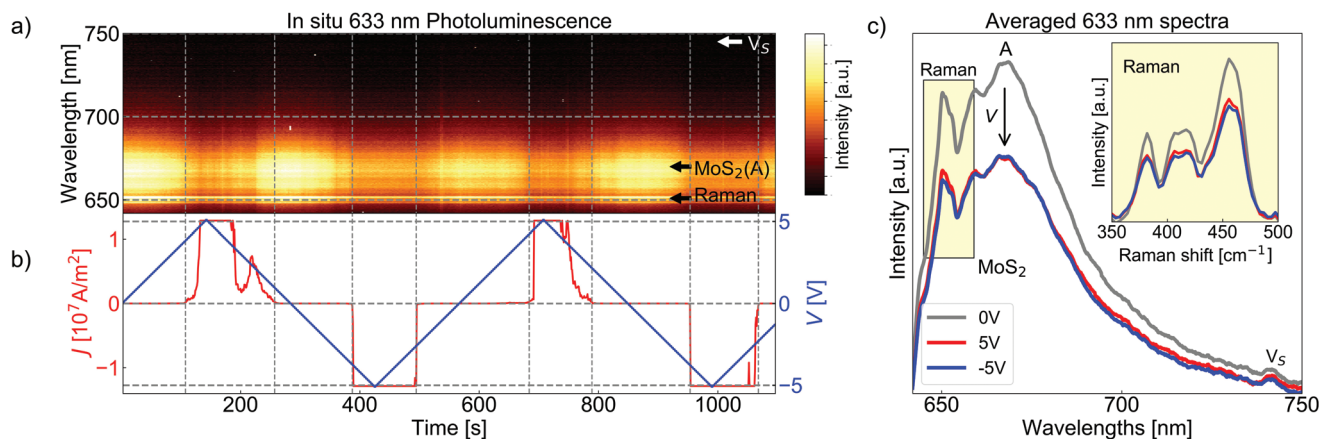
PL without Au background, and specifically on the dynamics of exciton A with voltage. Our in situ PL/Raman studies highlight two important behaviors. First, the PL signal is quenched when the sample becomes conductive (Figure 3), implying Au is in direct contact with MoS<sub>2</sub>.<sup>[20,47]</sup> Second, the advent of current does not shift the position of Raman peaks (Figure 3c – inset). We highlight that the passivation of  $V_S$  would result in the PL increase with bias<sup>[40,52]</sup> and the shift of  $A_{1g}$  Raman mode,<sup>[42]</sup> which is contrary to our findings. Those distinctive signatures confirm that  $V_S$  do not contribute to the process. Furthermore, they eliminate all switching mechanisms proposed in the literature except for metallic ions intercalation but without mediation of  $V_S$ , contrary to the data presented in Table 1.

## 2.4. In Situ Darkfield Scattering

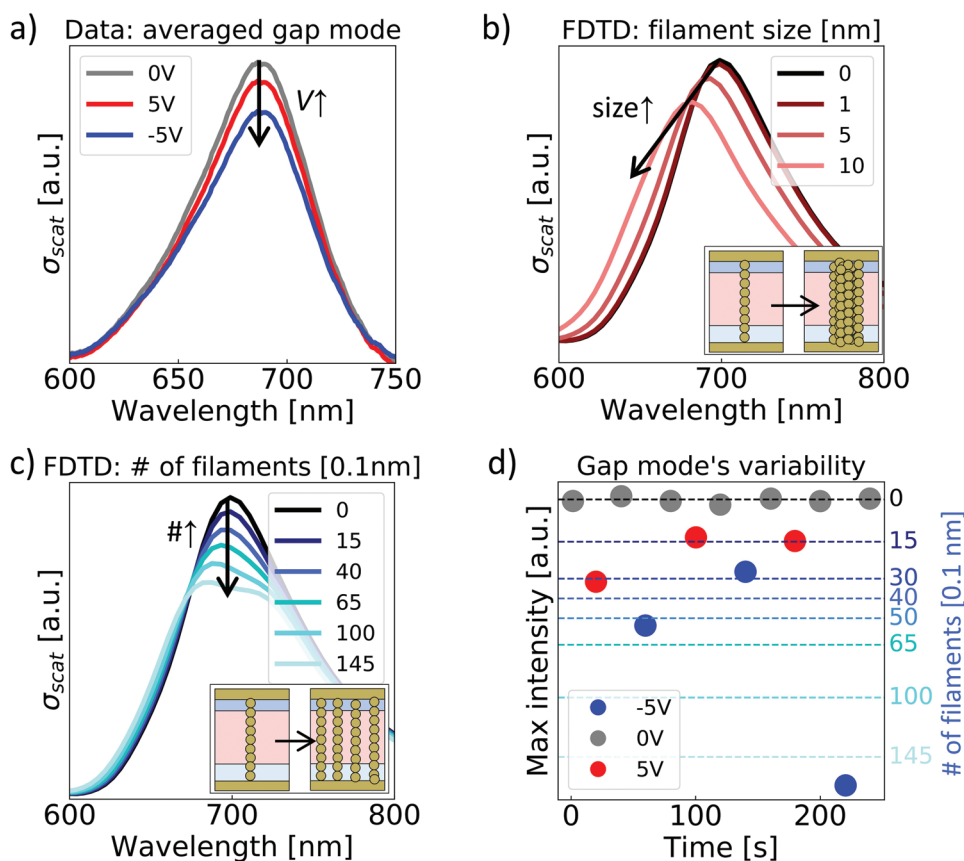
We complement our finding by investigating the evolution of the scattering signal with bias under white light illumination. This further expand the understanding of the switching mechanism, revealing the specific geometry of Au filaments

intercalating MoS<sub>2</sub>. Once the device is ON ( $\pm 5$  V), the plasmonic gap mode at  $\approx 690$  nm is reduced in intensity and no spectral shift is observed (Figure 4a).

To understand the mechanism behind this observation we simulate the geometry of the system through a commercial software (*Lumerical*) based on a finite-difference time-domain (FDTD) method.<sup>[63]</sup> We consider and simulate two possible scenarios determined by applied voltage: the creation of one Au filament which increases its size from 0 to 10 nm in diameter (Figure 4b) and the growth of several (1–145), equally sized (0.1 nm) and equally spaced Au filaments (Figure 4c). They both capture the mode intensity reduction observed experimentally. In fact, this confirms the intuitive picture where the formation of a Au bridge allows electrons to pass through the gap leading to an effective shorting of the plasmonic field confinement, hence reduction of its intensity. The two scenarios differ in their mode shift. The increase in size of one single filament would lead to a pronounced peak shift (Figure 4b), which we do not observe experimentally (Figure 4a). On the contrary, the growth of several and equally sized and spaced Au filaments (Figure 4c), shows almost no shift (for  $>40$  filaments a small field interaction



**Figure 3.** In situ PL/Raman (633 nm laser) characterization: a) optical signal time evolution, b) applied voltage profile with measured current density ( $J$ ), and c) spectra for 5, 0, and  $-5$  V averaged over many cycles. Inset: zoom on Raman spectra. Pulling of Au into MoS<sub>2</sub> by bias explains the observed quenching of PL and unshifted Raman signals.



**Figure 4.** Dark field analysis of the MoS<sub>2</sub> switch. a) Gap resonance decreases with voltage (data averaged over many cycles). b,c) FDTD simulations when b) one Au filament increases its size (0–10 nm in diameter) and c) several (1–145), equally atomic-sized (0.1 nm) and equally spaced Au filaments grow. d) Difference in a gap mode intensity reduction for individual cycles when a different number of 0.1-nm-thick filaments percolate MoS<sub>2</sub> (left axis: experimental data, right axis: simulation).

between nearby filaments is starting to mimic the field effect of a unique large filament causing a very minimal spectral shift). Therefore, this would confirm the picture of many nanofilaments (1–2 Au atoms thick) penetrating spaces between atoms in MoS<sub>2</sub> rather than one filament (or few, see Figure S4 in the Supporting Information) growing along a grain boundary, enlarging with voltage. Direct intercalation of Au atoms into interatomic distances in MoS<sub>2</sub> is possible as the size of a Au atom is  $\approx 1.4 \text{ \AA}$ <sup>[64]</sup> and the horizontal distance between atoms in the 2H phase of MoS<sub>2</sub> is  $\approx 3.2 \text{ \AA}$ .<sup>[65]</sup> Moreover, from our simulation we can estimate the number of filaments per each switching event, with a typical intensity reduction of  $\approx 7\%$  corresponding to  $\approx 15$  filaments in MoS<sub>2</sub>. Therefore, we can investigate how the gap mode's intensity change over several cycle (Figure 4d), observing a considerable statistical variation. This suggests that a different number of filaments is pulled by the same voltages over different switching events. We note that the effect is mildly less stochastic when Au drift is halted by ligands (5 V).

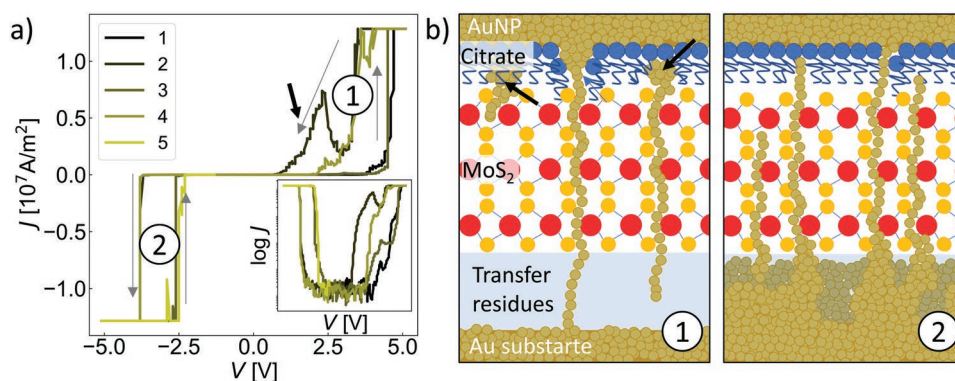
### 2.5. Electrical Characteristics

A typical current density–voltage ( $J$ – $V$ ) characteristic (Figure 5a) reveals threshold volatile resistive switching.<sup>[66]</sup> It is independent of a compliance level, and nonvolatility is not

observed even when we use current densities above those suggested in literature for memristive switching.<sup>[18,67]</sup> Moreover, we do not observe electro-forming cycle. MoS<sub>2</sub> recovers an OFF state for  $|V| < \approx 2.5 \text{ V}$ . High switching voltages of 4–5 V are most likely due to adlayers. We verify it by repeating electrical characterization with microsized electrodes without ligands, for which we obtain same stochastic threshold behavior with lower voltages of 2–3 V (Figure S5, Supporting Information). We note that the switching timescale in our operando method is different from that of commercial devices, which may operate at high frequencies. However, our experiment, in which we stress MoS<sub>2</sub> with pulses, results in same stochastic volatile threshold switching as observed in slower  $I$ – $V$  scans (Figure S5, Supporting Information), matching  $I$ – $V$  scans for a statistic of devices (Figure S6, Supporting Information).

### 3. Discussion

The ON/OFF switching is more stochastic, less sharp, and requires  $\approx 1 \text{ V}$  more bias when Au atoms are pulled from AuNP ( $V > 0$ , ⊕) rather than from a substrate ( $V < 0$ , ⊙) as visualized in Figure 5b. Since ligands impede the movement of Au atoms, they can introduce a “semimemristive” effect while stopping Au from retracting back to AuNP (black arrows in Figure 5). In



**Figure 5.** Understanding of electrical switching in MoS<sub>2</sub> nanosheets. a) Representative  $J$ - $V$  characteristics reveal a volatile threshold process, the insert presents data plotted with  $\log J$ . b) Resistivity change is driven by atomic-size Au filaments penetrating spaces between atoms in MoS<sub>2</sub>. ① Citrate ligands impede Au migration (higher switching voltages) and prevent Au retraction introducing a stochastic “semi-nonvolatility” (black arrows). ② Au atoms pulled from Au substrate result in a reproducible sharp threshold switching.

fact, most groups observe only volatile electrical switching in nanosheet MoS<sub>2</sub>,<sup>[23–25]</sup> and it is possible that the observation of nonvolatility in few layers thick MoS<sub>2</sub><sup>[13]</sup> might be associated with adlayers or transfer residues similar to citrate ligands. Indeed, it has been explicitly reported that memristive switching in vertically biased MoS<sub>2</sub> occurs only for a stack of monolayers,<sup>[17]</sup> thus when nanosheets are separated by transfer residues. This underlines that adlayer engineering might be a route to introduce a memristive effect in MoS<sub>2</sub>. Nevertheless, pristine MoS<sub>2</sub> provides superb sharp reproducible volatile switching characteristics with negligible leakage currents. It can be thus facilitated as a very successful electrical switch or a selector to solve sneak path problems occurring in memristive crossbar arrays.<sup>[68]</sup>

We would like to highlight that although participation of  $V_S$  in metal intercalation has been proposed by many groups,<sup>[5,13,17,18,20]</sup> we are the first to explicitly image the phenomenon in ambient conditions<sup>[18,20]</sup> and suggest that metal intercalation seems to be independent from  $V_S$ . We take into consideration that small modifications in Raman<sup>[42,49]</sup> and PL<sup>[39,40]</sup> associated with  $V_S$  might be present but undetectable. However, we believe that the used combination of three independent methods lowers chances of missing the signal change. Furthermore, defect-induced alterations in Raman has been previously reported using method with sensitivity alike ours.<sup>[50]</sup> Finally, FDTD simulations estimate up to 150 intercalating nanofilaments (Figure 4d), which corresponds to  $\approx 2\%$  of device’s area, and the passivation of 2% concentration of  $V_S$  is detectable in PL.<sup>[40]</sup>

Our discussion may apply to all transition metal dichalcogenides (TMD) due to comparable physical properties (energy structure, interatomic distances, chemical affinities etc.),<sup>[69,70]</sup> but it should not be generalized to all 2D materials, such as h-BN or graphene, which are not semiconductors. Indeed, literature data on memristive behavior for all TMD nanosheets is alike for MoS<sub>2</sub>.<sup>[13,67,71,72]</sup> In general, nonvolatility in a few layers thick TMD was observed by only one group and a memristive switching is usually mediated by some adlayers.<sup>[13,67,71,72]</sup> The techniques involve stacking many nanosheets using wet deposition (Ag/WSe<sub>2</sub>/Ag<sup>[67]</sup> and Pd/WSe<sub>2</sub>/Pt<sup>[73]</sup> cells), placing SiO<sub>2</sub> or Al<sub>2</sub>O<sub>3</sub> layer on top of MoTe<sub>2</sub> (Ti/MoTe<sub>2</sub>/Al<sub>2</sub>O<sub>3</sub>/Au and Ti/MoTe<sub>2</sub>/SiO<sub>2</sub>/Au switches),<sup>[74]</sup> and surface oxidation of WSe<sub>2</sub> (Ag/WO<sub>3-x</sub>/WSe<sub>2</sub>/graphene device).<sup>[71]</sup>

Finally, we note that the electrode’s material may affect the switching.<sup>[12,17]</sup> Here, we test Au to reproduce the architecture of the MoS<sub>2</sub> atomristors<sup>[20]</sup> and to achieve plasmonic enhancement. Although Au is less prone to intercalate into MoS<sub>2</sub> than other active metals,<sup>[17,18]</sup> e.g., Ag<sup>[5,18,23,24]</sup> and Cu,<sup>[17]</sup> we still observe metallic ion migration, with voltages higher than those reported for those electrode materials. This implies that the switching mechanism proposed here applies to other metallic contacts. Migration of metallic ions into MoS<sub>2</sub> has been observed not only for Ag<sup>[5,18]</sup> and Cu<sup>[17]</sup> but also for metals (e.g., Pt<sup>[75]</sup>) less prone to intercalate than Au. In general, it seems that metal intercalation is the only mechanism triggering memristive switching of vertically biased pristine MoS<sub>2</sub> nanosheets as the switching was not observed for nonmetallic electrodes such as carbon nanotube electrodes<sup>[18]</sup> and graphene,<sup>[12]</sup> where memristive effects may be achieved only by oxidation of MoS<sub>2</sub>.<sup>[12]</sup>

## 4. Conclusion

To our knowledge, we present the first characterization of nanoscale MoS<sub>2</sub>-based electrical switches at room temperature and in air. We propose a tool to access both PL and Raman, together with DF spectroscopy, for a true in operando investigation of MoS<sub>2</sub> switching mechanisms in real time. We prove that the drop in MoS<sub>2</sub>’s resistivity is triggered by Au atoms intercalating directly between Mo and S atoms forming many nanofilaments, most likely without the involvement of sulfur vacancies. We observe volatile switching with the potential for non-volatility by a careful adlayer engineering. Although a pristine MoS<sub>2</sub> nanosheet does not constitute a memristor, its reproducible sharp threshold switching characteristics make it a great candidate for a nanosized electrical switch or a selector eliminating leakage currents in memristive crossbars.

## 5. Experimental Section

**Device Fabrication:** At TU Wien single- and few-layer MoS<sub>2</sub> films were grown as described in,<sup>[76]</sup> see Section SD in the Supporting Information for details. Gold substrates (80 nm Au/10 nm Cr on 300 nm SiO<sub>2</sub>/Si)

were evaporated thermally in a custom-made evaporator. The MoS<sub>2</sub> film was transferred from the sapphire substrate onto the Au surface in a vacuum chamber, following the procedure.<sup>[61]</sup> For this purpose, a solution of polystyrene in toluene was spin-coated onto MoS<sub>2</sub> film. To delaminate the polymer film, the sample was immersed in a 30% solution of KOH. After delamination, the carrier polystyrene film was rinsed with MoS<sub>2</sub> film several times in DI water. To improve the adhesion between the carrier polymer film and the substrate, the sample was baked at 150 °C for ≈1 h. The polystyrene carrier film was then dissolved in toluene. Next, AuNPs (80 nm in diameter, *BBI Solutions*) were drop-casted onto the MoS<sub>2</sub> transferred on Au. Finally, an insulating PMMA layer was spin-coated and was etched down to ≈40 nm as confirmed on Si control samples by ellipsometry (J.A. Woollam, EC-400, 75 W Xe light source).

**Electrical Setup:** Biasing was achieved by contacting a single AuNP with a tipless semi-transparent cantilever (*Apex Probes*) coated by 3 nm Cr/6 nm Au (thermal evaporation). The cantilever was attached via a silver paste (SCP26G from *Electrolube*) to a custom mount operated by XYZR piezoelectric positioners (from *SmartAct*). The pressure of the top contact onto AuNP was ≈0.037 GPa, which did not affect the switching mechanism as reported.<sup>[29]</sup> The density of 1 AuNP / 100 μm<sup>2</sup> allowed for an electrical contact of a single AuNP (cantilever's dimensions are 30 μm × 100 μm). Electrical contact with the bottom Au substrate was achieved via a tungsten probe tip from *Lambda Photometrics Ltd* connected to a custom-made XYZ manual positioner from *Thorlabs*. Electrical signals from electrodes were sent via triaxial cables to the *Keithley 2634B* source meter, which allowed for low noise measurement down to 10 pA.

**Optical Setup:** The experiments were performed on the custom-made optical rig. All spectra were collected with a 2 s integration time utilizing a 100 × 0.8-NA objective from *Olympus* (LPM1anFLN). 633 and 444 nm CW single-longitudinal-mode lasers (*Integrated Optics*) were used for PL measurements. The laser power on samples was 1.5 μW. The 633-nm-excitation signals (PL/Raman) were sent into a spectrometer (*Andor*) coupled to a *Newton EMCCD* camera from *Oxford Instruments*. The 444 nm PL and DF signals were collected by an optical fiber to a dedicated spectrometer.

**FDTD Simulations:** Commercial *Lumerical* software from *Ansys* was used.<sup>[63]</sup> For all FDTD simulations AuNP's diameter was set to 80 nm with fixed facet diameter of 30 nm. To imitate used microscope configuration, light was injected at 55° with respect to a substrate. Complex permittivity of materials was taken from ref. [77] for Au and ref. [78] for MoS<sub>2</sub> (3 layers). Additionally, it was verified that MoS<sub>2</sub> refractive reported in other publications<sup>[79,80]</sup> gave same results. Based on literature values for PMMA,<sup>[81]</sup> polystyrene,<sup>[82,83]</sup> and citrate<sup>[84]</sup> the refractive index was set of ligand and transfer residues layers to *n* = 1.5. Based on the experimental data, for simulations of intercalating Au atoms a layout was used with 2 nm of MoS<sub>2</sub>, 0.5 nm of ligands surrounding AuNP, and 1 nm for transfer residues under MoS<sub>2</sub>. Intercalating filaments were simulated as cuboids (to avoid meshing errors) evenly distributed under AuNP's facet.

## Supporting Information

Supporting Information is available from the Wiley Online Library or from the author.

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## Conflict of Interest

The authors declare no conflict of interest.

## Data Availability Statement

The data that support the findings of this study are openly available in Apollo at <https://doi.org/10.17863/CAM.89994>, reference number 6317837.

## Keywords

electrical switches, MoS<sub>2</sub> nanosheets, nanoparticle on mirror, nonvolatility, plasmonics

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